

PTO-1449		<div style="border: 1px solid black; border-radius: 50%; padding: 5px; display: inline-block;"> <b>O I P E</b>  MAY 11 2006  U.S. PATENT &amp; TRADEMARK OFFICE </div>		Attorney's Docket Number RD27416-2	Serial Number 10/638,099	
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b> <b>LIST OF ITEMS</b> (Use several sheets if necessary)				Name of Applicant Gallucci et al.		
				Filing Date 08/07/2003	Group Art 1711	
<b>U.S. PATENT DOCUMENTS</b>						
Examiner Initial	Document Number	Date	NAME	Class	Subclass	Filing Date If Appropriate
tt	4754128	6/28/1988	Takeda et al.			/
	4942073	6/17/1990	Era et al.			
	5118573	6/2/1992	Tawara et al.			
	5297132	3/22/1994	Takano et al.			
	5330852	7/19/1994	Gerstenberg et al.			
	5512416	4/30/1996	Namba et al.			
	5525379	6/11/1996	Takada et al.			
✓	6183829	2/6/2001	Daecher et al.			
<b>U.S. PATENT APPLICATION PUBLICATIONS</b>						
Examiner Initial	Document Number	Date	NAME	Class	Subclass	Filing Date If Appropriate
tt	2002/0025443	2/28/2002	Ohno			
<b>FOREIGN PATENT DOCUMENTS</b>						
Examiner Initial	Document Number	Date	COUNTRY	Class	Subclass	TRANSLATION YES NO
tt	2099852	07-1993	Canada			X
<b>OTHER INFORMATION (including author, title, date, pertinent)</b>						
tt	Y.Barrell et al., "Expanding Thermal Plasma for Fast Deposition of Scratch-Resistant SiC <sub>x</sub> HyO <sub>z</sub> Films", Surface and Coatings Technology 180-181 (2004) 367-371					
	M.F.A.M. van Hest doctoral thesis, "High Rate Deposition of Silicone Oxide Like Films" pages 95-108, 133-154, 167-169 (2002)					
	10/638,145 Non-Final Office Action dated 10/07/2005 (18 pages)					
	10/638,145 Non-Final Office Action dated 03/21/2006 (12 pages)					
	JP03-248337; 11-1991; Abstract Only (2 pages)					
	JP01-232553; 09-1989; Abstract Only (2 pages)					
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	JP02-312020; 12-1990; Abstract Only (2 pages)					
	JP60-203489; 10-1985; Abstract Only (1 page)					
	JP63-108540; 05-1988; Abstract Only (2 pages)					
✓	JP63-201929; 08-1988; Abstract Only (2 pages)					
<b>EXAMINER</b> <i>Thao Tran</i>				<b>DATE CONSIDERED</b> <i>6/20/06</i>		
* EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not conformance and not considered. Include copy of this form with next communication to applicant.						